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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



Applicant(s): Chiang, Tony P.; Leaser, Karl F.; Brown, Jeffrey A.; Babcoke, Jason E.  
Assignee: Angstrom Systems, Inc.  
Title: Varying Conductance Out Of A Process Region To Control Gas Flux In An ALD Reactor  
Serial No.: 10/027592 Filing Date: December 19, 2001  
Examiner: Not yet known Group Art Unit: Not yet known  
Docket No.: M-11466-8C US

COMMISSIONER FOR PATENTS  
Washington, D. C. 20231

PRELIMINARY AMENDMENT

Dear Sir:

Please enter the following amendment prior to examination of the above-identified patent application.

IN THE CLAIMS

The following is a clean version of the amended claims. In accordance with 37 C.F.R. § 1.121(c)(1)(ii), Attachment A provides a marked up version of the amended claims.

Please amend the original Claims 15 and 16 as follows:

15. The method of Claim 1 wherein said varying a flux is part of a deposition sequence for depositing a thin film onto the substrate in the process chamber, the deposition sequence comprising:

introducing a first reactant gas into the chamber;

forming at least one monolayer on the substrate by adsorption of the first reactant gas;

LAW OFFICES OF  
SKJERVEN MORRILL  
MACPHERSON LLP

25 METRO DRIVE  
SUITE 700  
SAN JOSE, CA 95110  
(408) 453-9200  
FAX (408) 453-7979